

**MARKED-UP SPECIFICATION**

Please rewrite the sentence beginning on page 3, line 15 as --

In one embodiment, the second layer is Hydrogen [Hydroxy] Silsesquioxane.

Please rewrite the sentence beginning on page 6, line 10 as --

Materials appropriate for forming layer 130 include Hydrogen [Hydroxy] Silsesquioxane ( $\text{SiO}_x$ ; where x is less than 2).

**MARKED-UP CLAIMS**

9. (Amended) The photolithographic mask of claim 1, wherein the second layer is Hydrogen [Hydroxy] Silsesquioxane.

16. (Amended) The photolithographic mask of claim 15, wherein the second layer is Hydrogen [Hydroxy] Silsesquioxane.

36. (Amended) The photolithographic system of claim 35, wherein the second layer is Hydrogen [Hydroxy] Silsesquioxane.